

Title (en)
METHOD FOR DEPOSITION OF TITANIUM OXIDE BY A PLASMA SOURCE

Title (de)
VERFAHREN ZUR ABSCHIEDUNG VON TITANOXID DURCH EINE PLASMAQUELLE

Title (fr)
PROCEDE DE DEPOT D'OXYDE DE TITANE PAR SOURCE PLASMA

Publication
EP 1644554 A1 20060412 (FR)

Application
EP 04767517 A 20040630

Priority
• FR 2004001673 W 20040630
• FR 0307948 A 20030701

Abstract (en)
[origin: FR2857030A1] The deposition on a substrate of a coating with a base of semiconductor metal oxide, preferably titanium oxide, is carried out by depositing the coating with photocatalytic properties using chemical deposition in the vapor phase, preferably from a gas mixture containing at least one organometallic and/or metallic halogen of the metal oxide precursor. The deposition is plasma assisted. Independent claims are also included for: (a) A substrate coated by the above method; (b) A monolithic, multiple or laminated anti-stain and/or anti-mist glazing incorporating the substrate.

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C23C 16/40

IPC 8 full level
C23C 16/40 (2006.01)

CPC (source: EP KR US)
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